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**FACSIMILE COVER SHEET**

DATE: December 17, 2003  
TO: Examiner Kilday, A.U. 2829  
FROM: George Loud  
RE: USSN 09/808,016  
TOTAL NUMBER OF PAGES (INCLUDING COVER SHEET): 2  
FACSIMILE NUMBER: 703 746-3904

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**MESSAGE**

Ms. Kilday,

As you requested in telephone conversation of earlier today, I am herewith transmitting page 7 of our response filed October 2, 2003 in USSN 09/808,016.

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consisting of ammonia, hydrazine, amines, and amino compounds, ~~and their derivatives~~ into contact with a surface of a substrate, on which an insulating film is exposed, to chemically activate the surface;

(b) subsequent to step (a), reforming the chemically activated surface as formed in step (a) by contacting the chemically activated surface with a gas or an aqueous solution containing an oxidizing agent selected from the group consisting of Hydrogen hydrogen peroxide, ozone, Oxygen oxygen, nitric acid, and sulfuric acid, ~~and their derivatives~~ to form an oxide film on the chemically activated surface;

(c) subsequent to step (b), forming an insulating film by CVD on the oxide film as formed in step (b).